

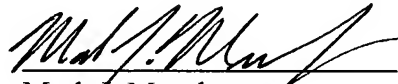
one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method". This limitation is supported in the specification for example at page 10, ln. 29 - page 11, ln. 3. The claims of the '886 patent do not recite such a limitation. Therefore, it is respectfully submitted that the claims of the present application are patentably distinct from those in the '886 patent, and no double patenting is present in this application. Accordingly, it is requested that this rejection be withdrawn, and the application allowed.

Please charge our deposit account 50/1039 for any further fee due for this amendment.

Favorable reconsideration is earnestly solicited.

Respectfully submitted,

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Marked-up copy of the amendments made herein:

IN THE CLAIMS:

Please amend the claims as follows:

36. (Amended) A method of manufacturing a display device comprising the steps of:
forming a thin film transistor over a substrate;
forming a pixel electrode electrically connected to the thin film transistor;
forming a body with a textured surface on the pixel electrode; and
forming a light reflection film on the body with the textured surface by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

43. (Amended) A method of manufacturing a display device comprising the steps of:
forming a thin film transistor over a substrate;
forming a pixel electrode electrically connected to the thin film transistor;
forming a body with a textured surface on the pixel electrode;
forming a light reflection film on the body with the textured surface by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method;
and

flattening a surface of the light reflection film by a CMP process.

50. (Amended) A method of manufacturing a display device comprising the steps of:
forming a thin film transistor over a substrate;
forming a pixel electrode electrically connected to the thin film transistor;
forming a body with a textured surface on the pixel electrode; and

forming a light reflection film on the body with the textured surface by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method, wherein the light reflection film has a higher refractive index than the body with the textured surface.

57. (Amended) A method of manufacturing a display device comprising the steps of:
forming an insulated gate field effect transistor on a semiconductor substrate;
forming a pixel electrode electrically connected to the insulated gate field effect transistor;
forming a body with a textured surface on the pixel electrode; and
forming a light reflection film on the body with the textured surface by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

64. (Amended) A method of manufacturing a display device comprising the steps of:
forming an insulated gate field effect transistor on a semiconductor substrate;
forming a pixel electrode electrically connected to the insulated gate field effect transistor;
forming a body with a textured surface on the pixel electrode;
forming a light reflection film on the body with the textured surface by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method;
and
flattening a surface of the light reflection film by a CMP process.

71. (Amended) A method of manufacturing a display device comprising the steps of:
forming an insulated gate field effect transistor on a semiconductor substrate;
forming a pixel electrode electrically connected to the insulated gate field effect transistor;

forming a body with a textured surface on the pixel electrode; and

forming a light reflection film on the body with the textured surface by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method,

wherein the light reflection film has a higher refractive index than the body with the textured surface.